## FEB 21 10 39 AV 166 Approved For Release 2003/01/28 : CIA-RDP78B04770A002608090001-5

		NPIC PROJECT NO.
	-C-O-N-F-I-D-E-N-T-I-A-L- CLASSIFICATION	P&DS RESPONSIBLE COMPON
RECEIPT RB/OS	SUPPORT/SERVICE REQUIREMEN	DISSEMINATED RB/OS
(The following info is requ	uired when rqmts are levied by ex	ternal organization:3)
OFFICE	DATE OF RQMT	CONTROL NO.
NPIC DIV/DETACH PROCESSING	RQMT PROJ OFF	PHONE
SUPPORT REQUESTED OF	PRIORITY	DATE REQUIRED
	uired when rqmts are levied for in	25
DIV/STAFF P&DS	DATE OF RQMT 18 February 19	66 CONTROL NO.
SUPPORT REQUESTED OF	P&DS PROJ OFF	
PRIORITY	DATE REQUIRED	1 April 1969
1. BACKGROUND INFORMATION:	•	
Non-photo interpretati	ion project. It will result in: ); X Basic service only.  Printer-Processor Fly-Away Kit (	
		D14207
Photographic; Repr	CE REQUESTED: Support from NPIC roduction; Mensuration; Carlo (Include statement as to estimate the contact prints, enlarges	will probably consist of: raphics; ADP; Editing; mated amount of work required of
Photographic; Repr X Other (explain below) support component(s); i.e., Design, development	CE REQUESTED: Support from NPIC roduction; Mensuration; Grant as to estimate the contract of t	will probably consist of: raphics;ADP;Editing; mated amount of work required of gements, boards, etc.)
Photographic; Repr X Other (explain below) support component(s); i.e., Design, development	CE REQUESTED: Support from NPIC roduction; Mensuration; Grant for the contact prints, enlar, and fabrication of three (3) Rap	will probably consist of: raphics;ADP;Editing; mated amount of work required of gements, boards, etc.)
Photographic; Repr X Other (explain below) support component(s); i.e., Design, development	CE REQUESTED: Support from NPIC roduction; Mensuration; Grant for the contact prints, enlar, and fabrication of three (3) Rap	will probably consist of: raphics;ADP;Editing; mated amount of work required of gements, boards, etc.)
Photographic; Repr X Other (explain below) support component(s); i.e., Design, development	CE REQUESTED: Support from NPIC roduction; Mensuration; Grant for the contact prints, enlar, and fabrication of three (3) Rap	will probably consist of: raphics;ADP;Editing; mated amount of work required of gements, boards, etc.)
Photographic; Repr X Other (explain below) support component(s); i.e., Design, development Processor Fly-Away F	CE REQUESTED: Support from NPIC roduction; Mensuration; Grand function; Mensuration; Grand function of three (3) Rap and fabrication of three (3) Rap Kit based on the Diazo Process.  (If immediate support is require	will probably consist of: raphics; ADP; Editing; mated amount of work required of gements, boards, etc.) id Interpretation Printer
Photographic; Repr X Other (explain below) support component(s); i.e., Design, development Processor Fly-Away F	CE REQUESTED: Support from NPIC roduction; Mensuration; Grand function; Mensuration; Grand function of three (3) Rap and fabrication of three (3) Rap Kit based on the Diazo Process.  (If immediate support is require	will probably consist of: raphics; ADP; Editing; mated amount of work required of gements, boards, etc.) id Interpretation Printer
Photographic; Repr X Other (explain below) support component(s); i.e., Design, development Processor Fly-Away F	CE REQUESTED: Support from NPIC roduction; Mensuration; Grand function; Mensuration; Grand function of three (3) Rap and fabrication of three (3) Rap Kit based on the Diazo Process.  (If immediate support is require	will probably consist of: raphics; ADP; Editing; mated amount of work required of gements, boards, etc.) id Interpretation Printer
Photographic; Reprover the processor Fly-Away Flore (Processor Fly-Away Flore)  3. URGENCY JUSTIFICATION: must be made on this form.)	CE REQUESTED: Support from NPIC roduction; Mensuration; Grand (Include statement as to estimate and fabrication of three (3) Rapkit based on the Diazo Process.  (If immediate support is required)	will probably consist of: raphics; ADP; Editing; mated amount of work required of gements, boards, etc.)  id Interpretation Frinter  ed a statement of justification
Photographic; Reprover the processor Fly-Away Fly-Resorred Bernston Support component Processor Fly-Away Fly-Resorred Bernston State of the processor Fly-Away Fly-Resorred Bernston State of the processor Fly-Resorred Bernston Fly	CE REQUESTED: Support from NPIC roduction; Mensuration; Grand (Include statement as to estimate and fabrication of three (3) Rapkit based on the Diazo Process.  (If immediate support is required)	will probably consist of: raphics; ADP; Editing; mated amount of work required of gements, boards, etc.)  id Interpretation Frinter  ed a statement of justification
Photographic; Reprover Section Selow Support component(s); i.e.,  Design, development Processor Fly-Away Forcessor Fly-Away Fly-Aw	CE REQUESTED: Support from NPIC roduction; Mensuration; Grand (Include statement as to estimate and fabrication of three (3) Rapkit based on the Diazo Process.  (If immediate support is required)	will probably consist of: raphics; ADP; Editing; mated amount of work required of gements, boards, etc.) id Interpretation Printer

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